



Micro-bumping vs. Hybrid Bonding: Pros/Cons in Terms of Power Delivery

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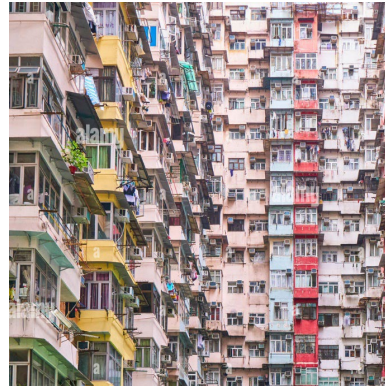
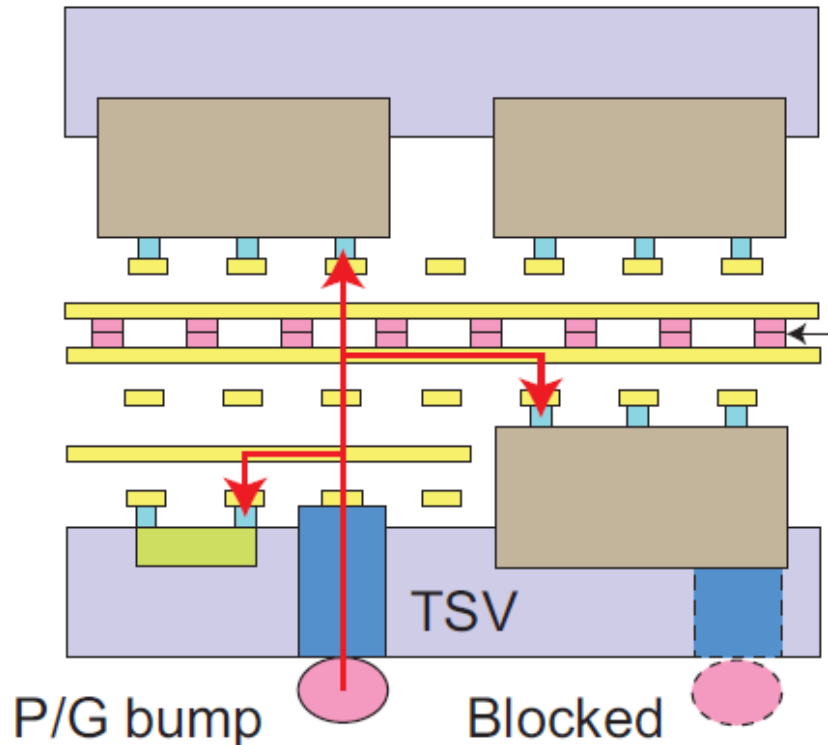


Outline

- Motivation
- Executive Summary
- Design and Simulation Setting
- Power Integrity Analysis Details



Power Delivery Challenges in 3D ICs



Higher power density



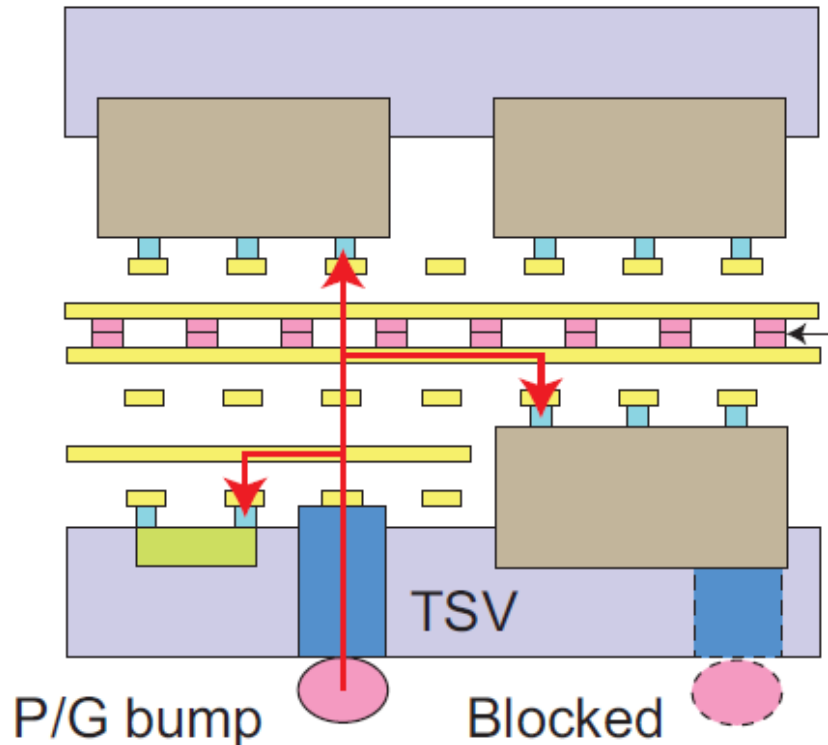
Fewer power bumps/pads



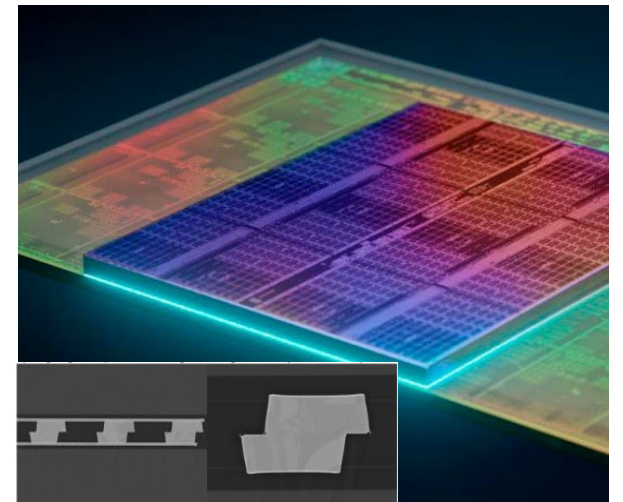
More resistive power paths



Die Bonding: Two Leading Contenders



Micro-Bumping, Intel
50um pitch demonstrated



Hybrid Bonding, TSMC
9um pitch demonstrated



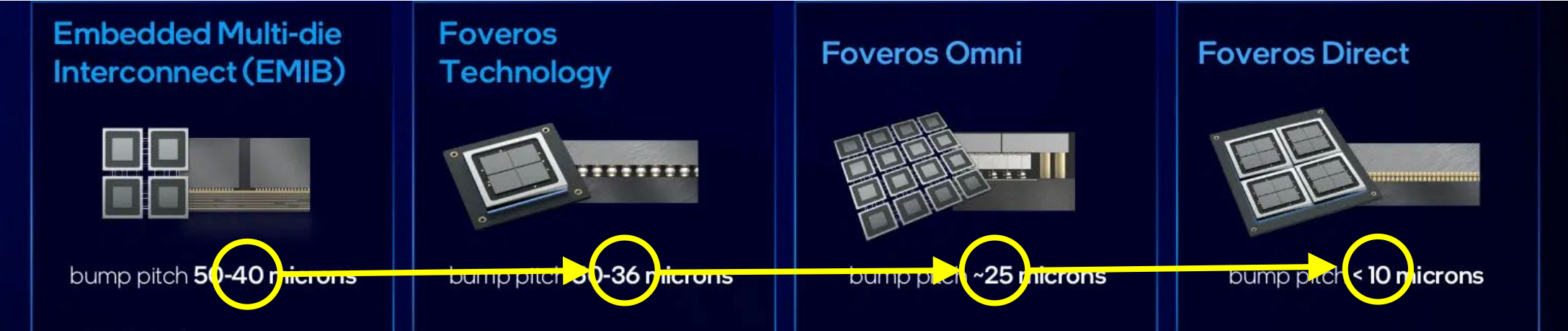
3D Bonding Roadmap

Numbers from public domain

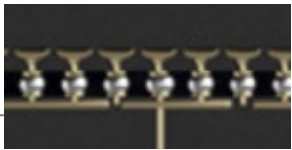
TSMC SoIC Scaling Roadmap					
Generation	SoIC1	SoIC2	SoIC3	SoIC4	SoIC5
Bond Pitch	9-micron	6-micron	4.5-micron	3-micron	2-micron
Bandwidth Density ⁽¹⁾	1x	2x	3.4x	6.05x	11.54x
Energy Efficiency	1x	1x	1.17x	1.33x	1.44x

OK, bond pitch will reduce. Great.

What is the impact on power delivery?

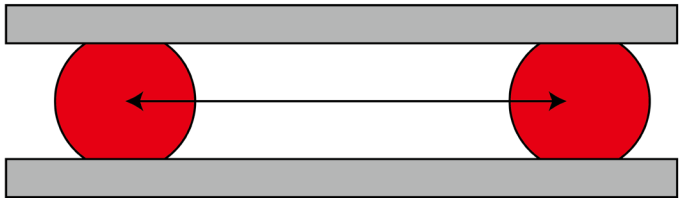


Our Choices for Pitch



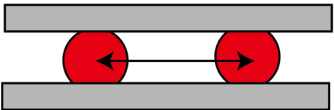
micro-bumping

present

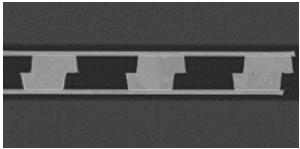
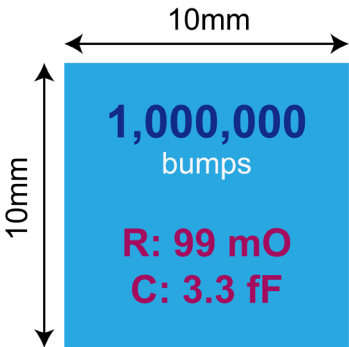
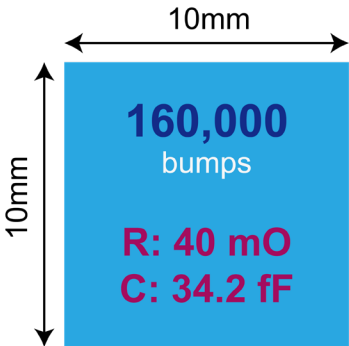


25um

future



10um

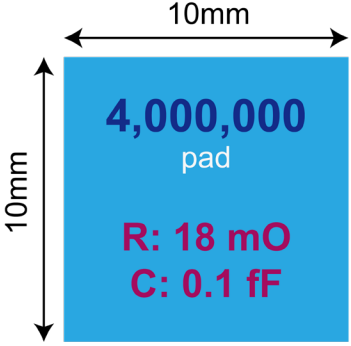


hybrid bonding

present



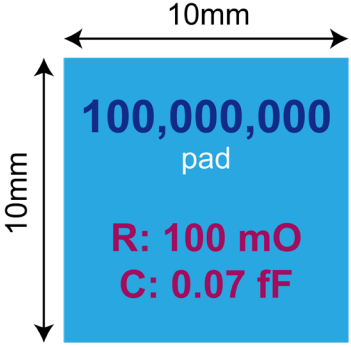
5um



future



1um



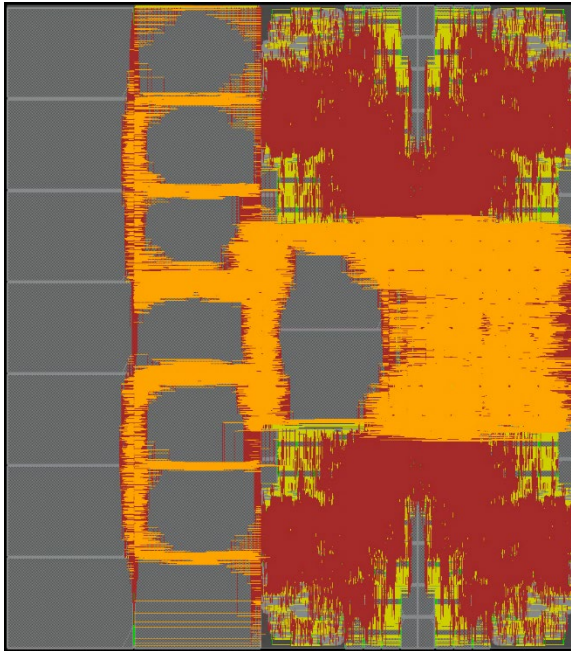


Executive Summary



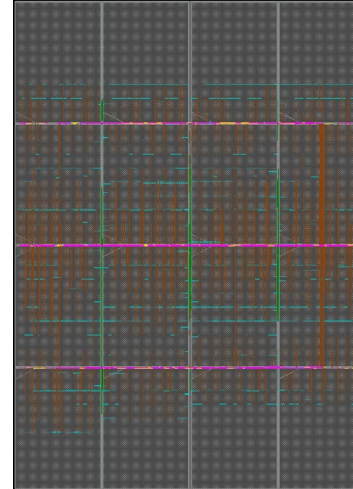
We Do Full-Chip Designs

Architecture	Technology	Quality	Design Flow	3D Config
ARM A53 Quad Core	16nm	GDS + Sign-off	Macro-3D	L2-on-Logic



2D IC GDS (6 metal)

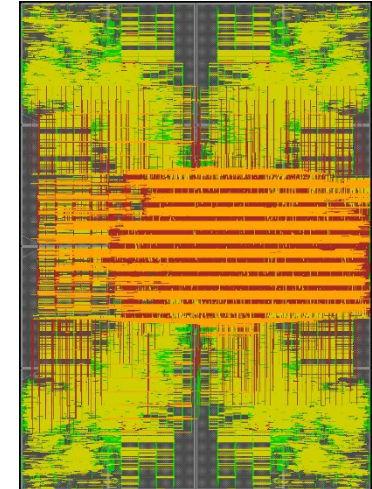
memoryc



**signal bump
(1,188)**



logic



3D IC GDS (7M + 6L metals)



2D vs. 3D Iso-Performance Comparison

- Iso-performance (low power apps)
 - Target freq. is fixed to 0.6GHz for all designs

← tier partitioning is identical →

		Innovus 2D	U-bump 25um	U-bump 10um	H-bond 5um	H-bond 1um
N	Static IR-drop (mV)	12.78	41.48	42.91	27.54	24.43
P	Power (mW)	537.3	536.4	537.1	466.3	450.6
P	Fmax (GHz)	0.600	0.600	0.600	0.600	0.600
A	Footprint (mm)	2.0 x 2.2	1.2 x 1.7	1.2 x 1.7	1.2 x 1.7	1.2 x 1.7
T	Tmax (°C)	51.60	59.52	59.54	57.63	57.20



2D vs. 3D Max-Performance Comparison

- Max-performance (high performance apps)
 - Fmax is pushed to the upper limit for each design

← tier partitioning is identical →

		Innovus 2D	U-bump 25um	U-bump 10um	H-bond 5um	H-bond 1um
N	Static IR-drop (mV)	14.25	46.63	68.10	74.22	68.23
P	Power (mW)	598.6	651.1	888.9	1267.1	1214.5
P	Fmax (GHz)	0.630	0.694	0.977	1.172	1.218
A	Footprint (mm)	2.0 x 2.2	1.2 x 1.7	1.2 x 1.7	1.2 x 1.7	1.2 x 1.7
T	Tmax (°C)	52.34	62.63	69.07	79.31	77.89





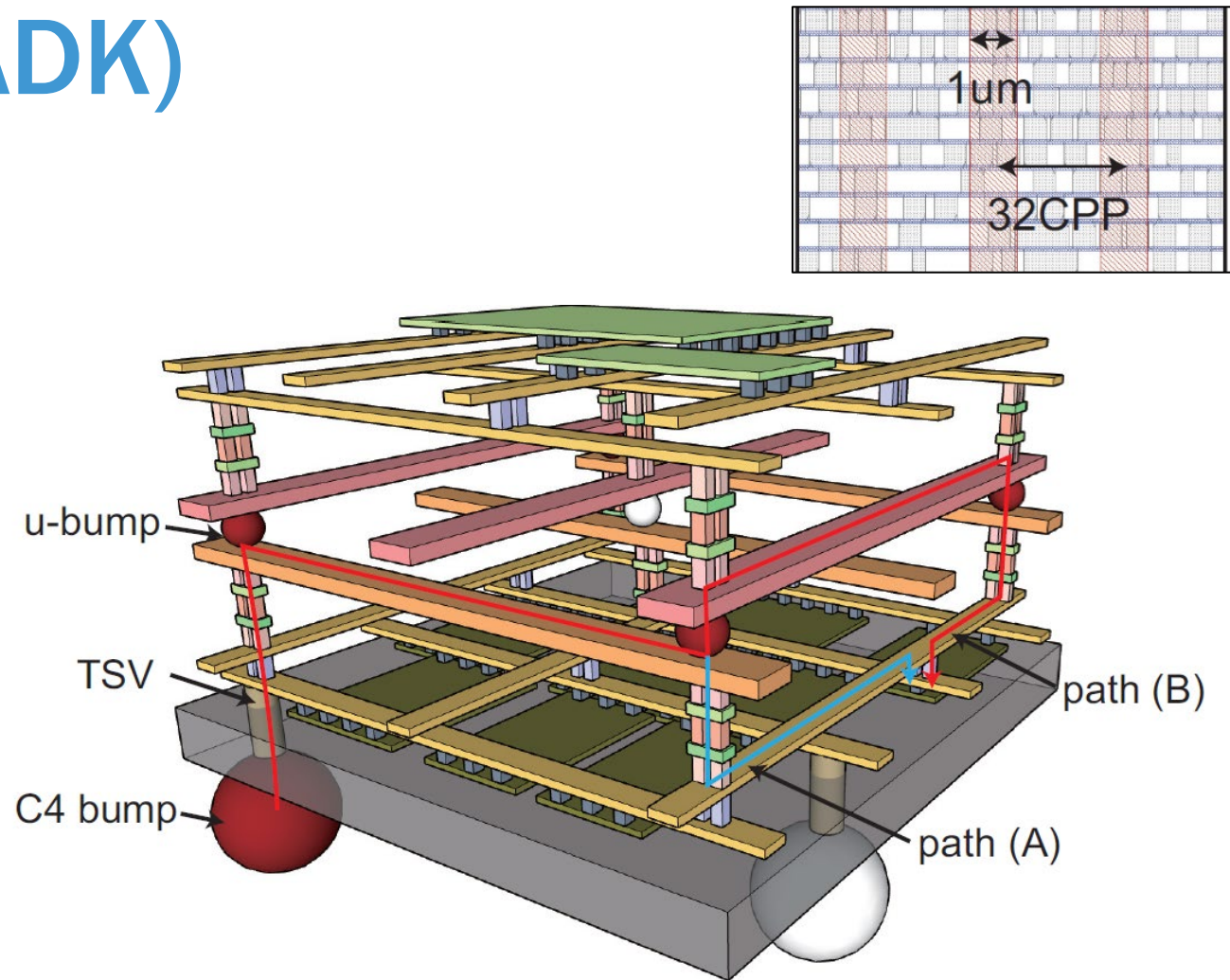
Design and Simulation Setting



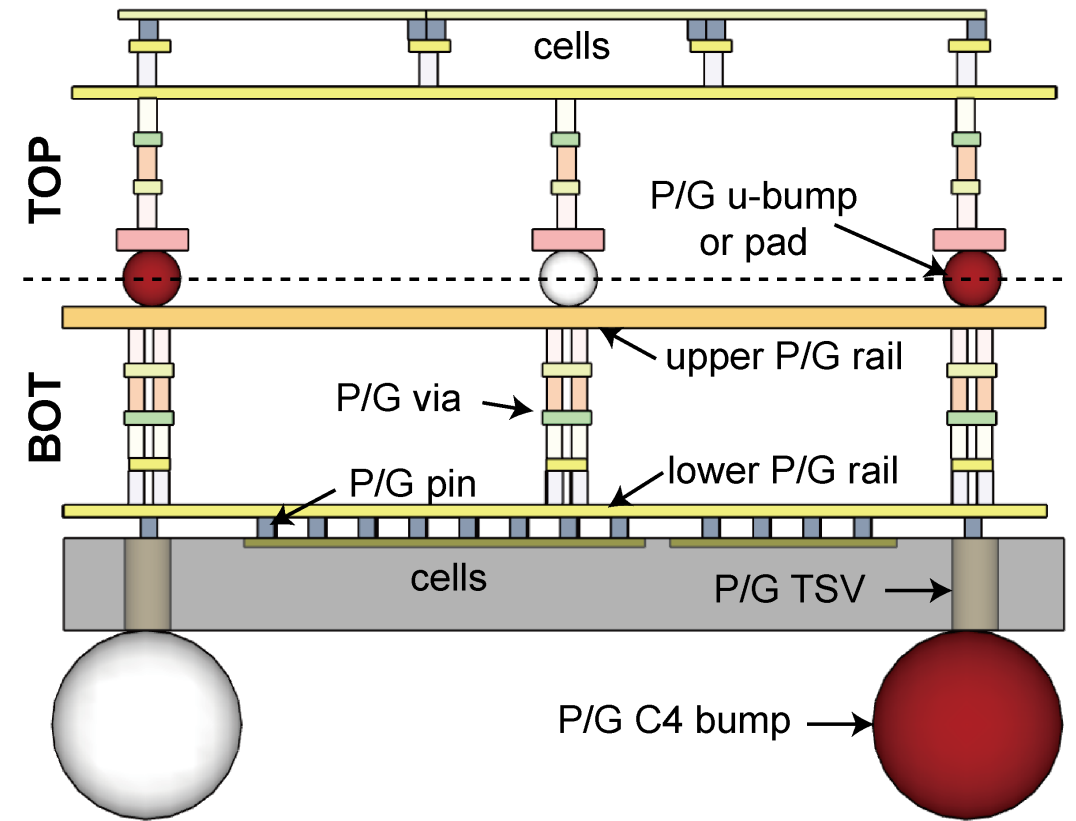
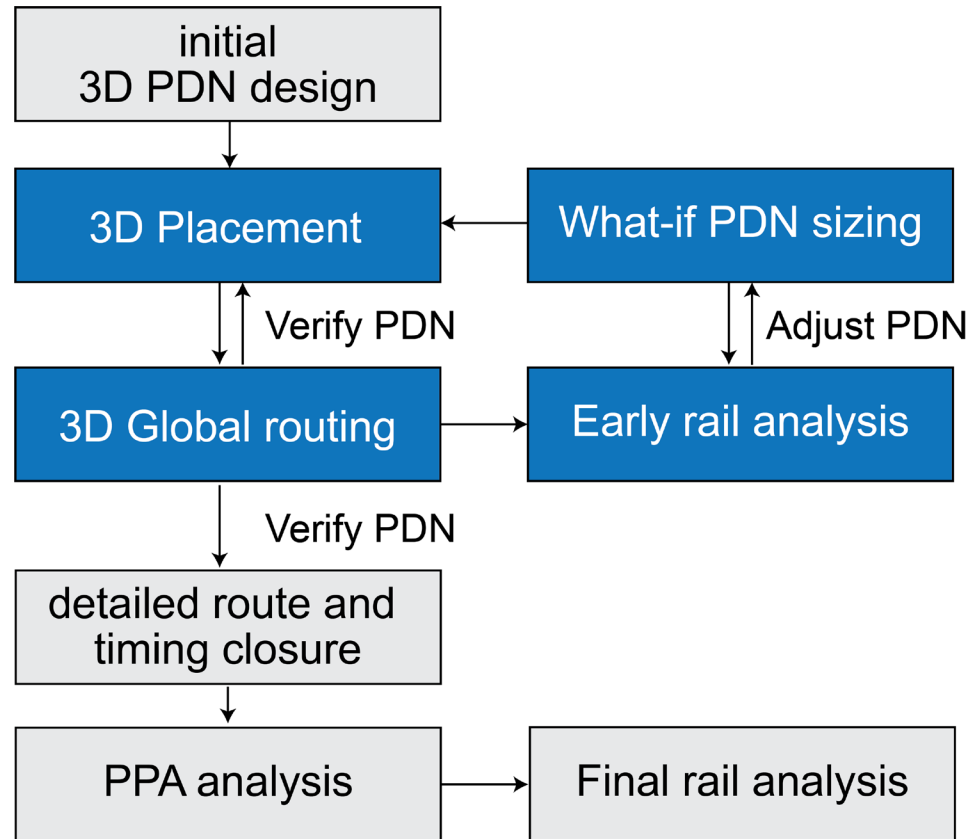
Assembly Design Kit (ADK)

3D Technology Setup

Metal layer #	7M
Vdd	800mV
PDN layer	M1, M5, M6, M7
Rail pitch / width (um)	2.8 / 1
C4 pitch (um)	100
C4 RC (mΩ / fF)	18 / 38
TSV pitch (um)	10
TSV RCL (mΩ / fF / pH)	47 / 86 / 48

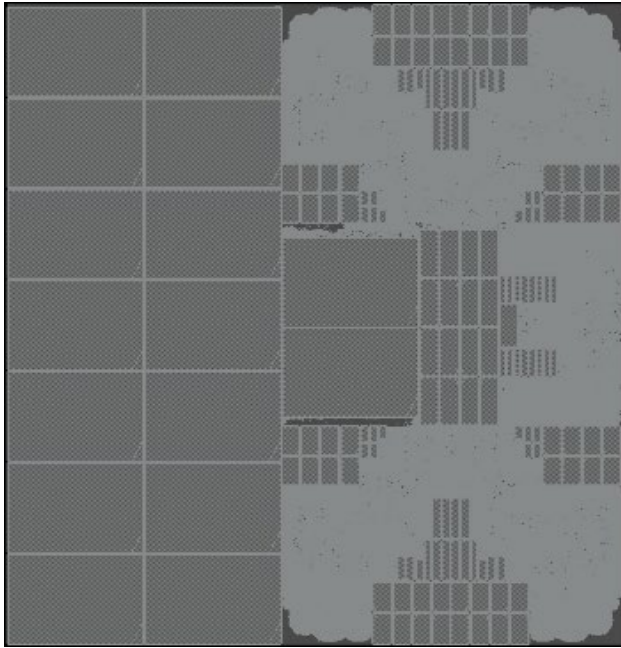


PDN Design Flow

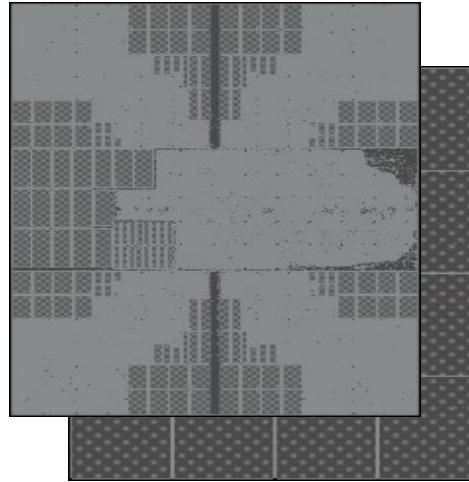


Full-chip 3D Design Flow

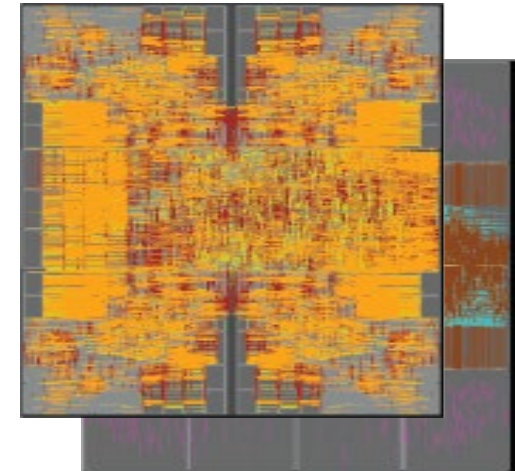
- Leverage commercial 2D IC tools (as much as possible)
- Then add missing pieces



2D IC placement
[existing 2D IC tool]



Gate-level tier partitioning
[innovation]



3D IC routing and timing closure
[innovation]





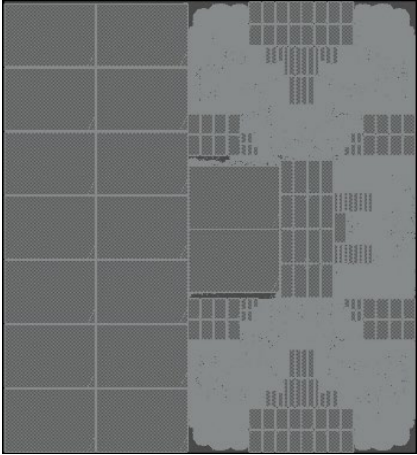
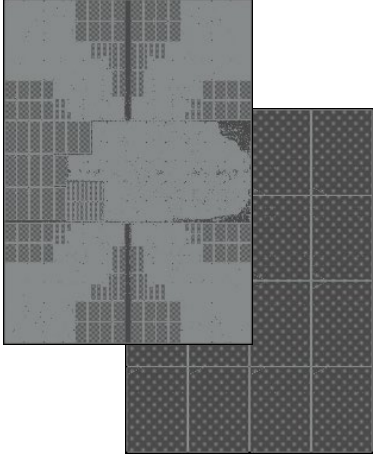
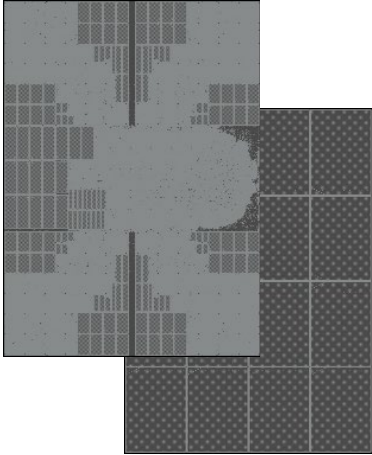
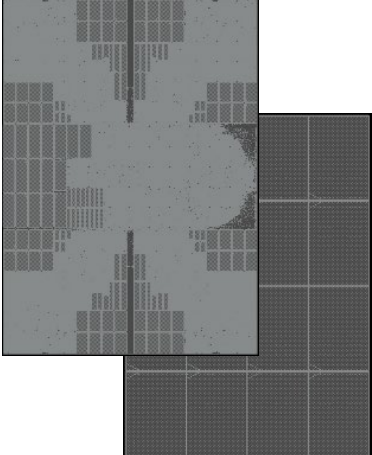
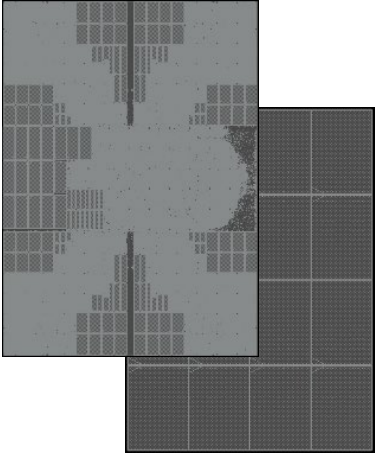
Power Integrity Analysis Details



Five Full-Chip GDS Layouts

- Placement

- Identical tier partitioning, but different placement

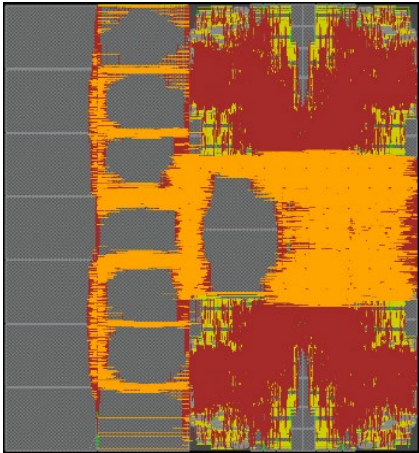
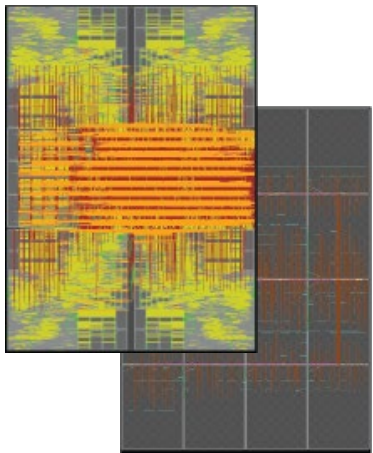
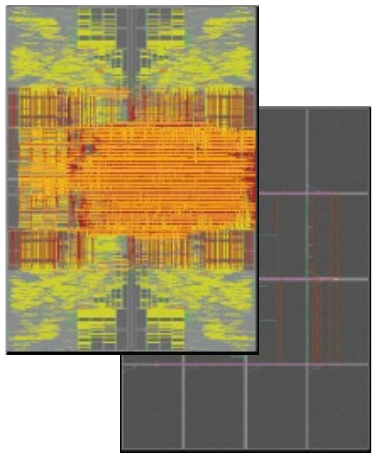
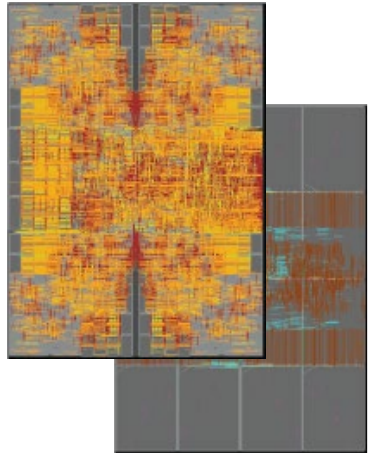
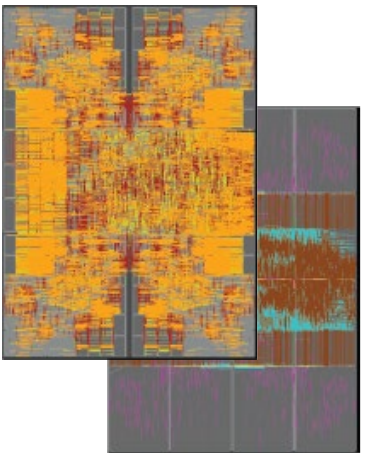
				
2D	U-bump 25um	U-bump 10um	H-bond 5um	H-bond 1um



Five Full-Chip GDS Layouts

- Routing

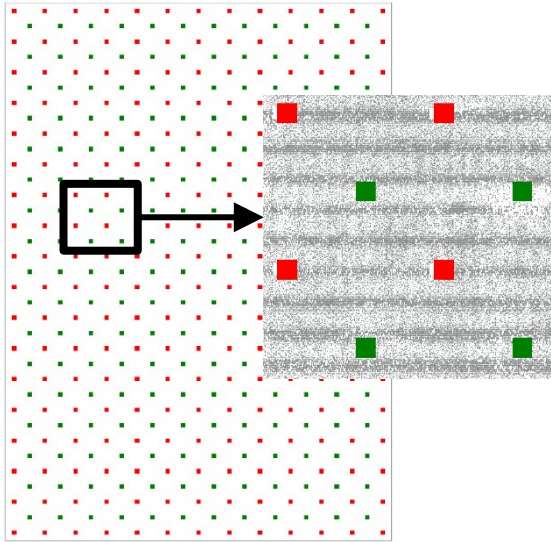
- Identical tier partitioning, but different routing

				
2D	U-bump 25um	U-bump 10um	H-bond 5um	H-bond 1um

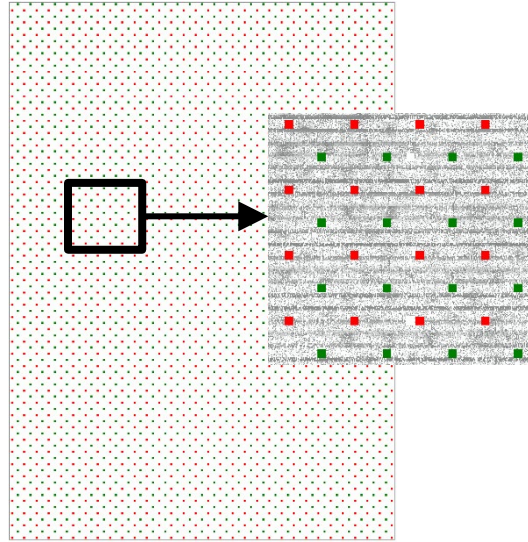


P/G Bump/Pad Placement

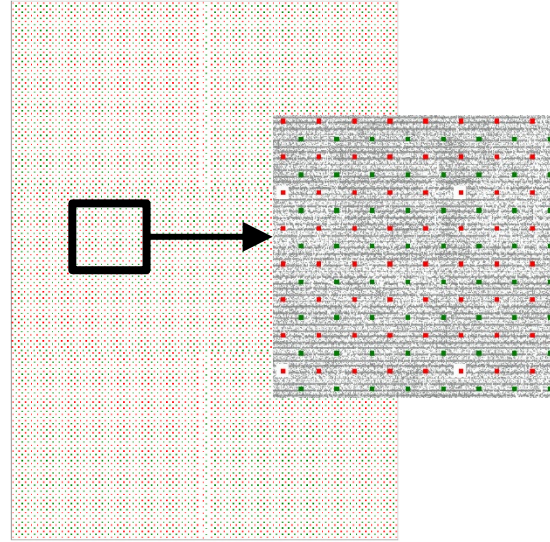
Red: power, Green: ground



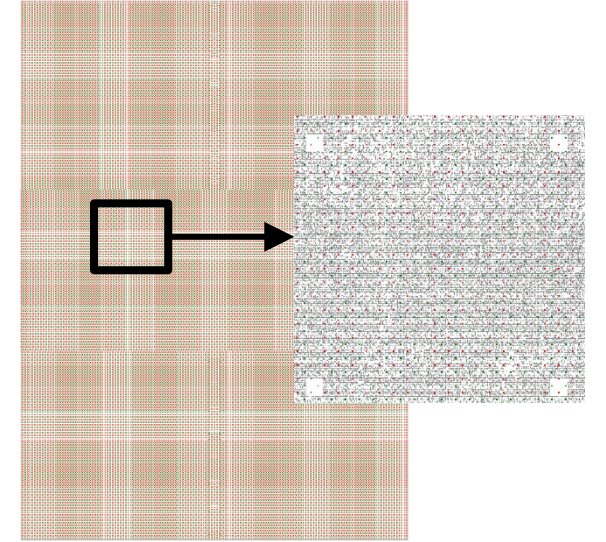
U-bump 25um



U-bump 10um



H-bond 5um

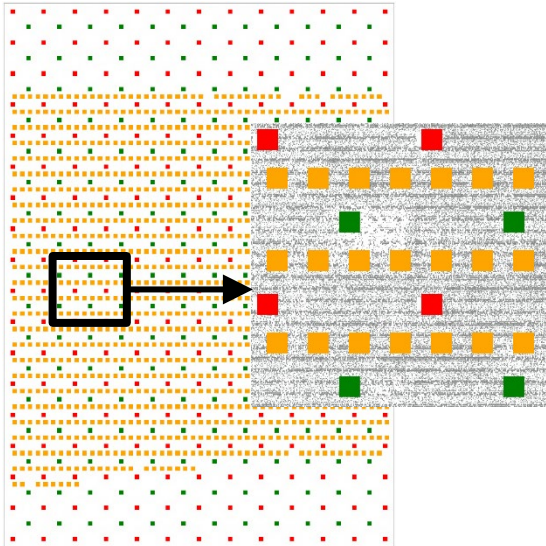


H-bond 1um

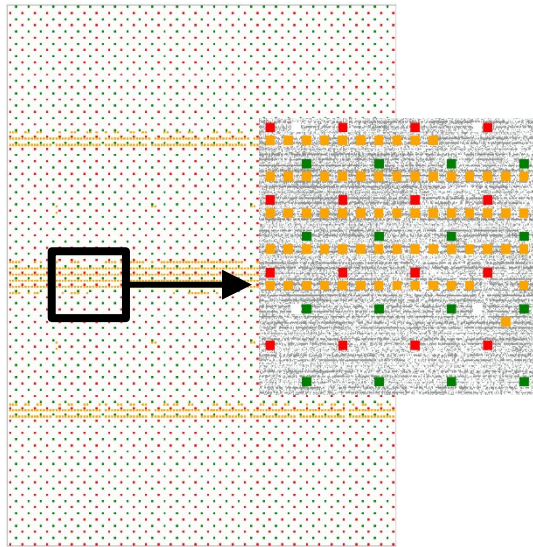


P/G/S Bump/Pad Placement

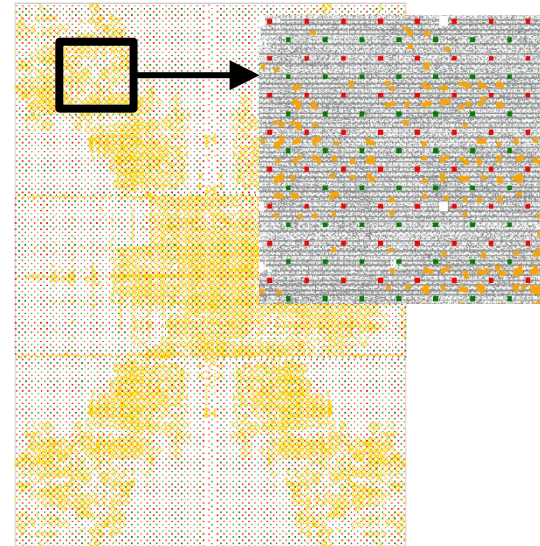
Red: power, Green: ground, Yellow: signal



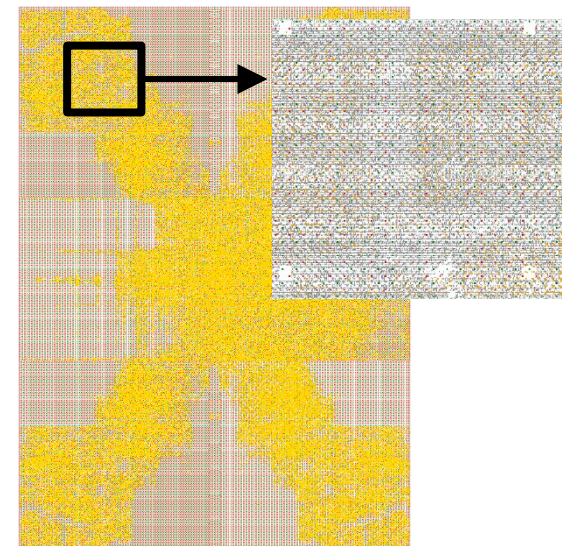
U-bump 25um



U-bump 10um



H-bond 5um

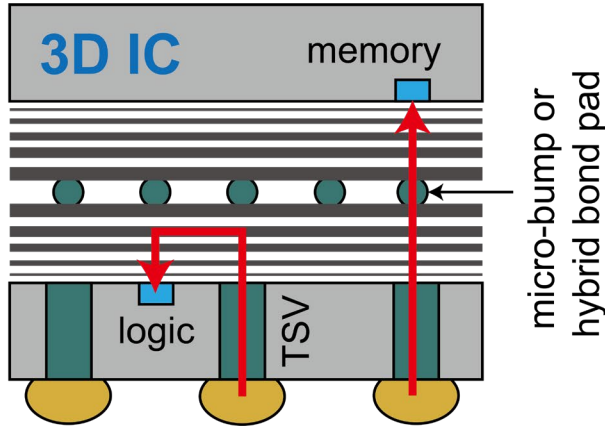
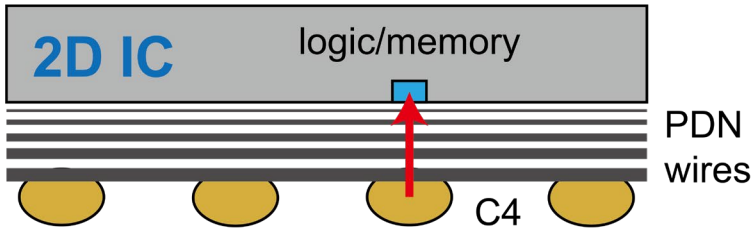


H-bond 1um

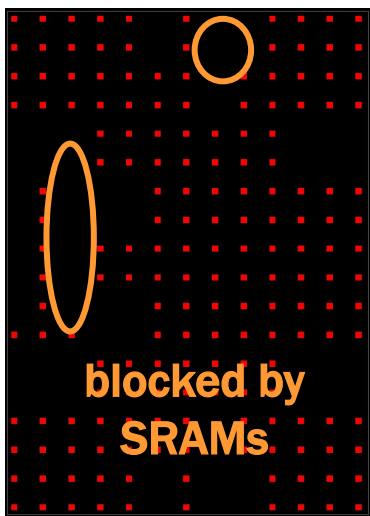


PDN Usage Summary

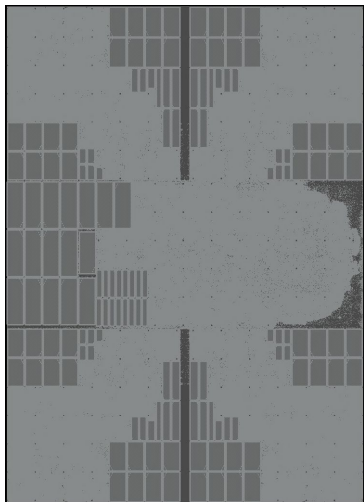
	Innovus 2D	U-bump 25um	U-bump 10um	H-bond 5um	H-bond 1um
# P/G C4	460	234	234	234	234
PDN wire area (mm ²)	3.26	3.33	3.34	3.33	3.34
# P/G bump/pad used	-	438	3K	11K	139K



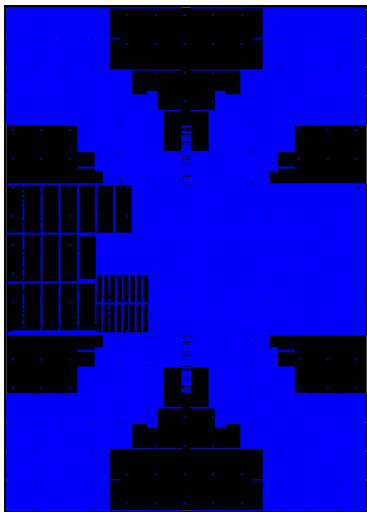
PDN Routing: Logic Tier



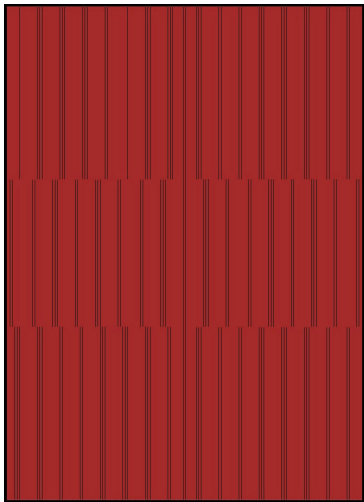
C4 (pitch = 100um)



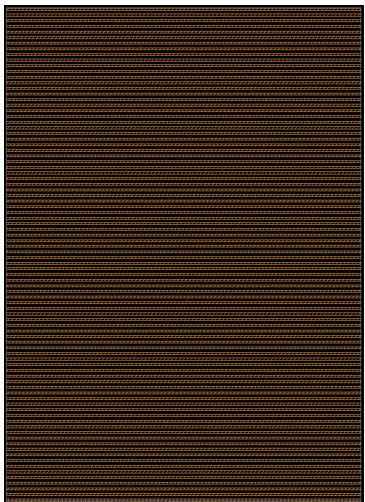
placement



M1 P/G (31.7%)



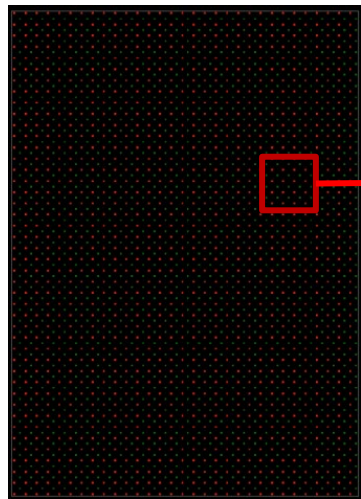
M5 P/G (70.0%)



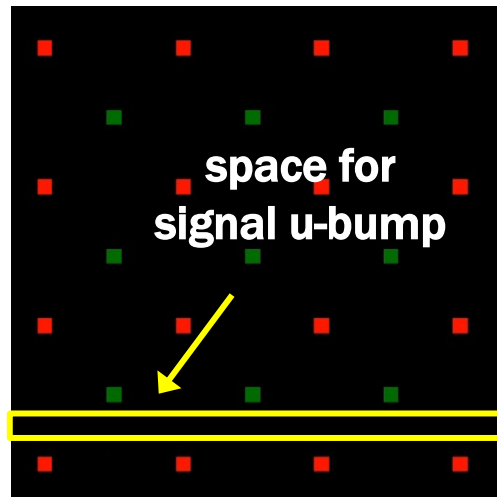
M6 P/G (71.3%)



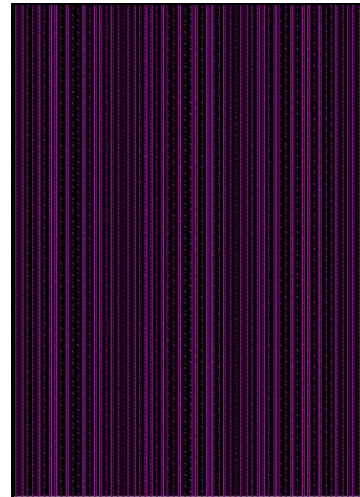
PDN Routing: Memory Tier



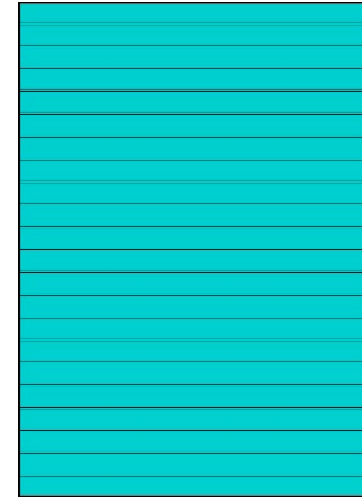
P/G u-bump



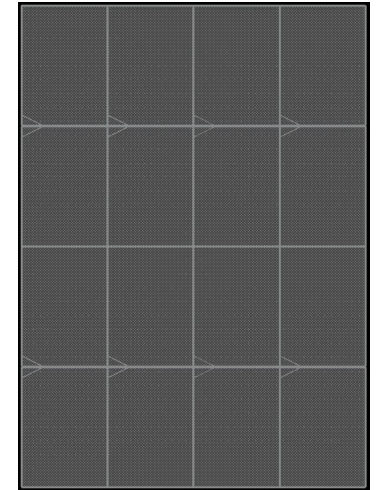
red = P, green = G



M7 P/G (71.1%)



M6 P/G (71.0%)



placement

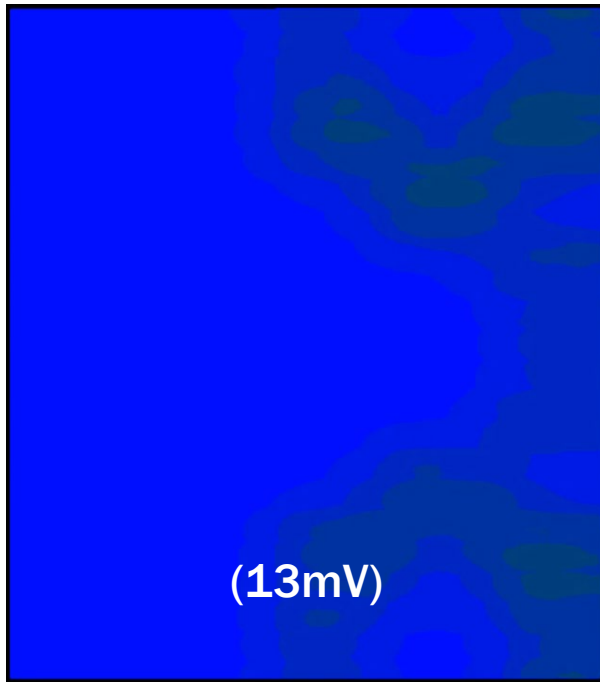




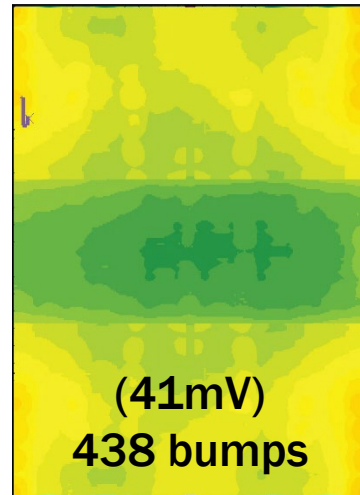
Iso-Performance Design Analysis



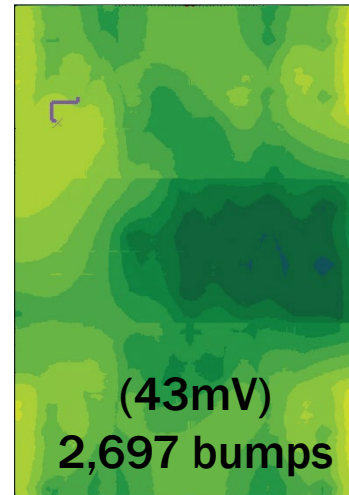
Static IR-drop Maps



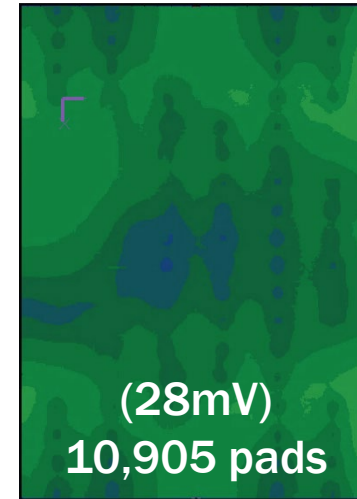
2D



U-bump 25um



U-bump 10um



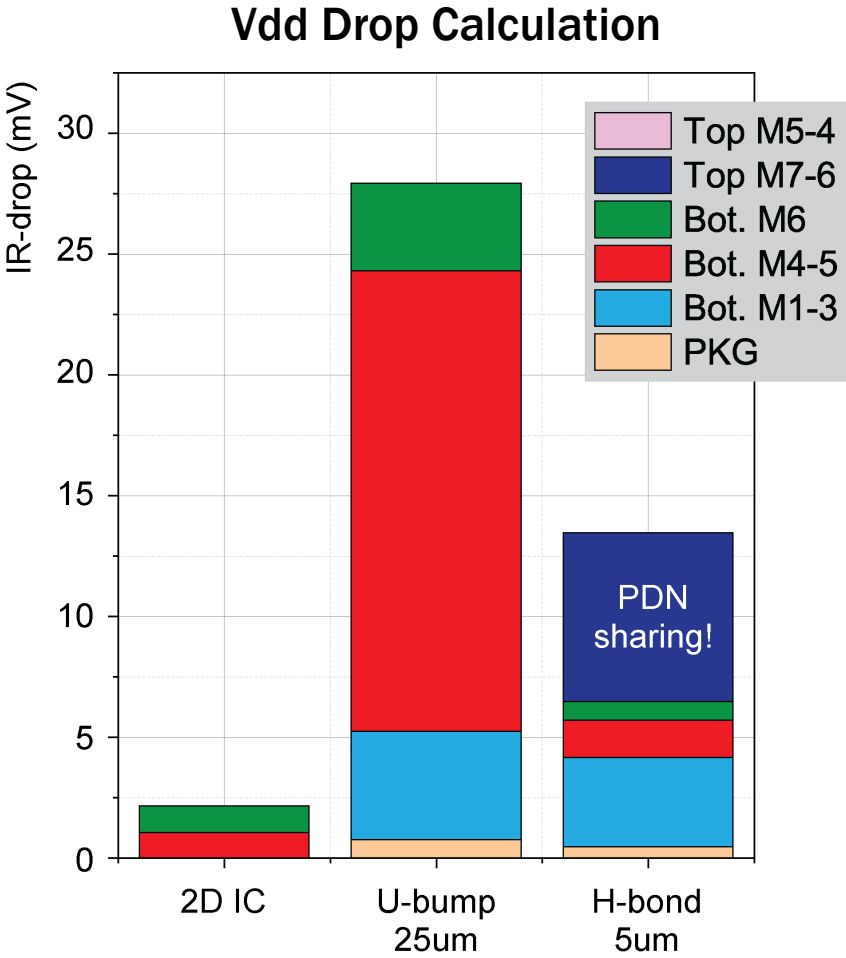
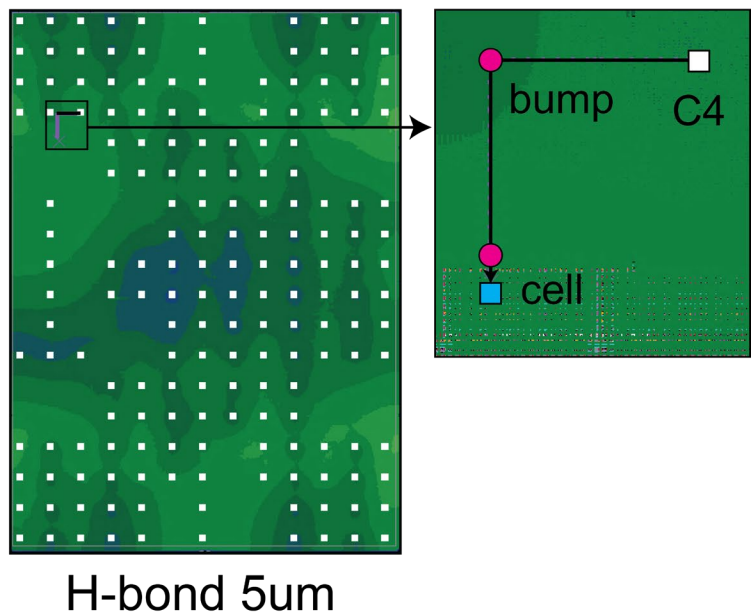
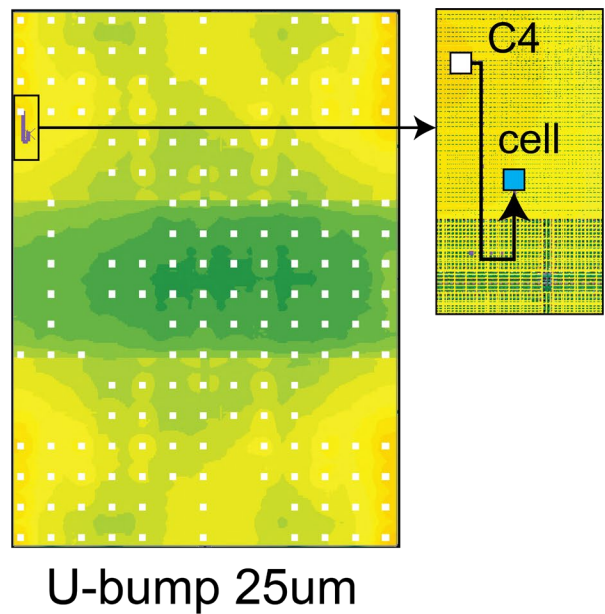
H-bond 5um



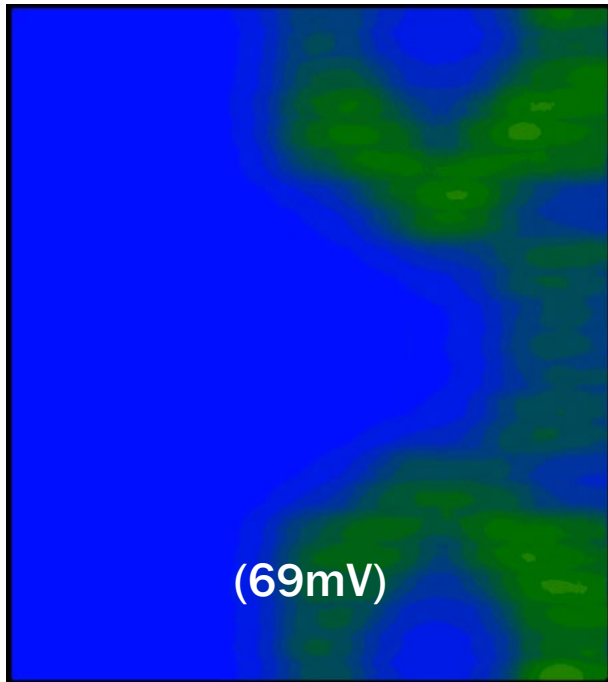
H-bond 1um



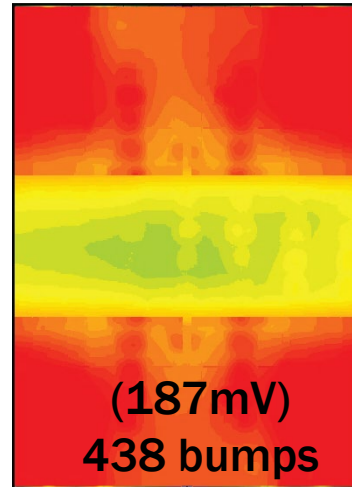
Least Resistive Path



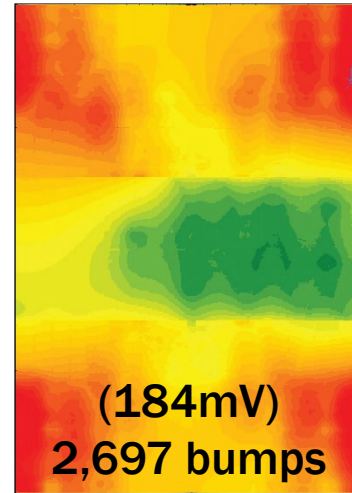
Dynamic IR-drop Maps



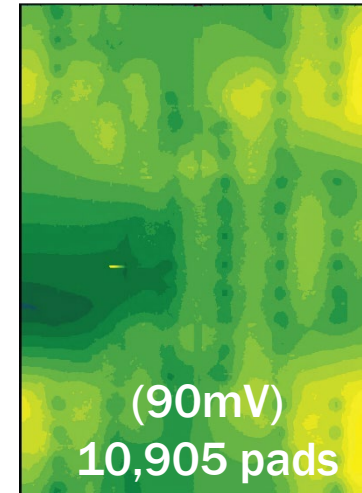
2D



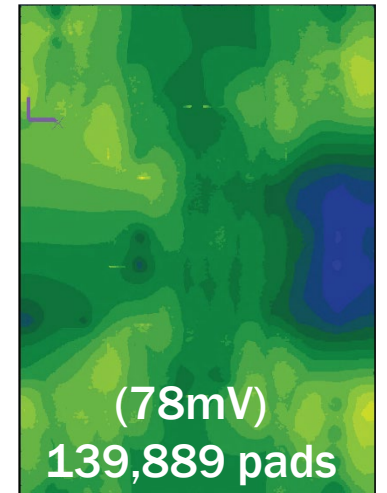
U-bump 25um



U-bump 10um



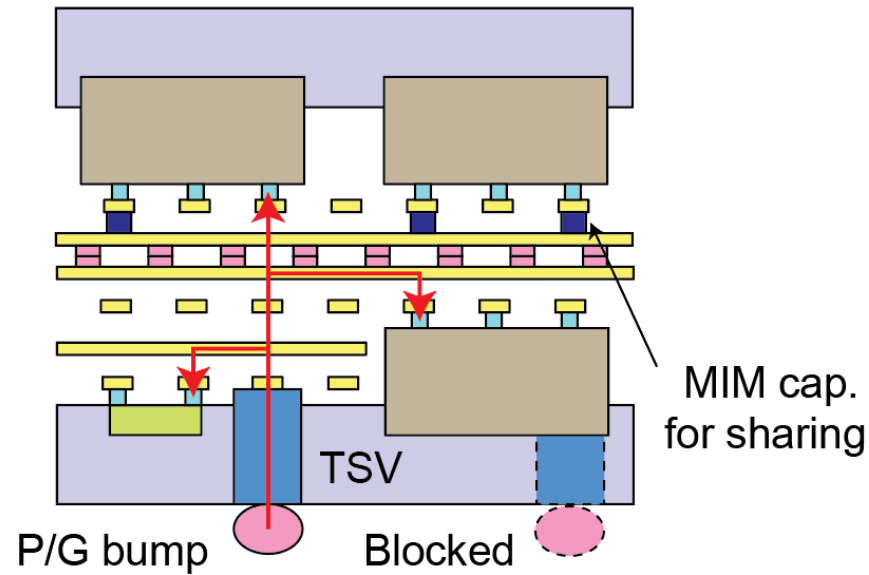
H-bond 5um



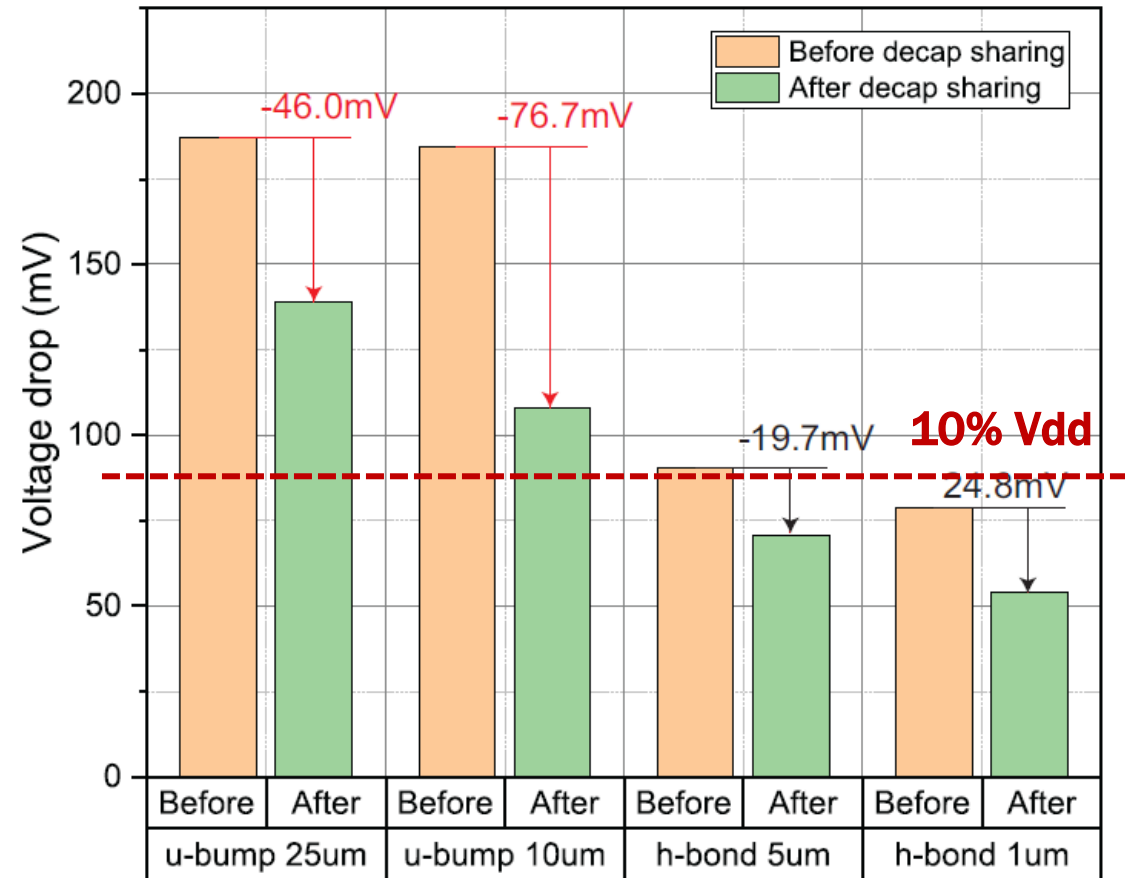
H-bond 1um



MIM Decaps Help

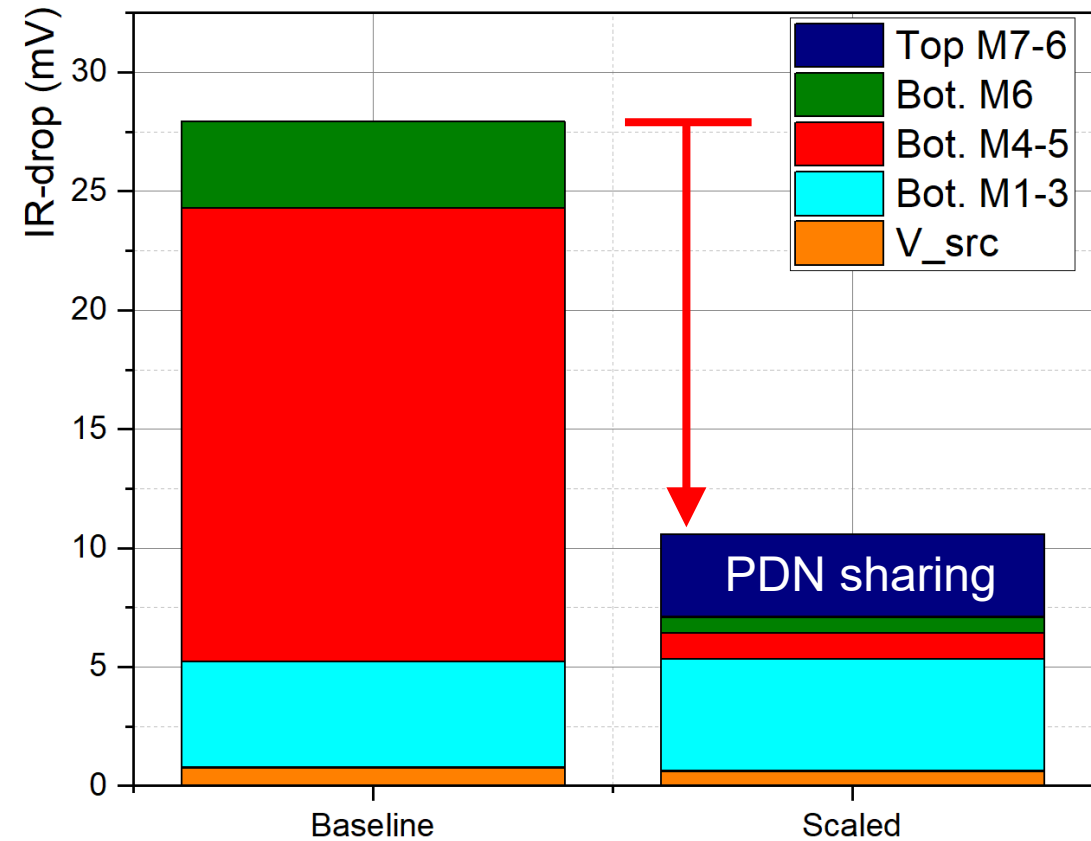


In logic tier BEOL (M5-M7)
Cap. density = 40fF/mm²
Total inserted: 678nF



What If M45 Resistivity Reduced?

- Scale wire resistivity
 - 50% on M4 & M5 (U-bump 25um)
 - Vdd drop reduces from 27mV to 11mV
 - More inter-tier rail sharing occurs



Conclusion

- Power delivery is harder for 3D ICs
 - Mainly due to smaller footprint (= fewer C4s)
 - Micro-bumping vs. hybrid bonding: it depends on several factors
- 3D IC IR-drop under **iso-performance**
 - Micro-bumping was worse: due to fewer bumps
- 3D IC IR-drop under **max-performance**
 - Hybrid bonding was worse: due to faster chip

